

Amendment submitted in response
to Office Action mailed 12/07/2004
U.S. Pat App. No. 10/813,913
March 4, 2005
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Amendments to the Abstract:

Please replace the Abstract as filed with the following corrected Abstract:

In a plasma processing system, a method of inspecting a contact opening of a contact formed in a first layer of the substrate to determine whether the contact reaches a metal layer that is disposed below the first layer is shown. The method includes flowing a gas mixture into a plasma reactor of the plasma processing system, the gas mixture comprising a flow of a chlorine containing gas. The method also includes striking a plasma from the gas mixture; and exposing the contact to the plasma. The method further includes detecting whether metal chloride is present is in the contact opening after the exposing.